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Christophe Gorecki
Anand Krishna Asundi
Wolfgang Osten
Editors

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Contents

ix Conference Committee

SESSION 1 DIGITAL HOLOGRAPHY

- 7718 03 **Deep-ultraviolet digital holographic microscopy for nano-inspection** [7718-02]
A. Faridian, D. Hopp, G. Pedrini, W. Osten, Univ. Stuttgart (Germany)
- 7718 04 **Digital holography from shadowgraphic phase estimates** [7718-03]
F. Eilenberger, Friedrich-Schiller-Univ. Jena (Germany); D. Pliakis, Technical Univ. of Crete (Greece); S. Minardi, T. Pertsch, Friedrich-Schiller-Univ. Jena (Germany)
- 7718 05 **Fast noncontact surface roughness measurements up to the micrometer range by dual-wavelength digital holographic microscopy** [7718-04]
J. Kühn, Ecole Polytechnique Fédérale de Lausanne (Switzerland); E. Solanas, S. Bourquin, Lyncée Tec SA (Switzerland); J.-F. Blaser, L. Dorigatti, T. Keist, Trimos SA (Switzerland); Y. Emery, Lyncée Tec SA (Switzerland); C. Depeursinge, Ecole Polytechnique Fédérale de Lausanne (Switzerland)
- 7718 06 **Managing the depth of focus in 3D imaging through controlled distortion of digital holograms** [7718-05]
M. Paturzo, P. Memmolo, A. Finizio, P. Ferraro, CNR-Istituto Nazionale di Ottica Applicata (Italy)

SESSION 2 NEW ASPECTS IN MICROTOPOGRAPHY MEASUREMENTS I

- 7718 08 **Investigation of enhanced 2D field-stitching method as a simulation-tool for line-edge roughness in scatterometry** [7718-07]
B. Bilski, K. Frenner, W. Osten, Univ. Stuttgart (Germany)
- 7718 0A **CCD-ARS set-up: a comprehensive and fast high-sensitivity characterisation tool for optical components** [7718-09]
M. Zerrad, M. Lequime, C. Deumié, C. Amra, Institut Fresnel Marseille, UMR CNRS (France) and Univ. de Marseille (France) and Domaine Univ. de St Jérôme (France)
- 7718 0B **Interferometric precision with Fourier-based deflectometry** [7718-10]
D. Beguin, X. Dubois, L. Joannes, X. Hutsebaut, LAMBDA-X sa (Belgium); P. Antoine, Univ. Catholique de Louvain (Belgium)

SESSION 3 NEW ASPECTS IN MICROTOPOGRAPHY MEASUREMENTS II

- 7718 0C **A deflectometric sensor for the on-machine surface form measurement and adaptive manufacturing** [7718-11]
S. Krey, I. Erichsen, I. Mahns, W. D. van Amstel, TRIOPTICS GmbH (Germany); K. Vielhaber, Fraunhofer-Institut für Produktionstechnologie (Germany)

- 7718 0D **Statistical signatures of random media: application to selective cancellation of scattered light** [7718-12]
J. Sorrentini, M. Zerrad, C. Amra, Institut Fresnel Marseille. UMR CNRSTIC (France) and Univ. Paul Cézanne, Univ. de Provence (France) and Domaine Univ. de St Jérôme (France)
- 7718 0E **Object-adapted fringe projection technique on scattered data interpolation** [7718-13]
W. Zhou, J. Peng, M. Chen, Y. Yu, Shanghai Univ. (China)

SESSION 4 INSPECTION OF MEMS I

- 7718 0F **Next-generation test equipment for micro-production (Invited Paper)** [7718-14]
K. Gastinger, L. Johnsen, SINTEF IKT (Norway); M. Kujawinska, M. Jozwik, Warsaw Univ. of Technology (Poland); U. Zeitner, P. Dannberg, Fraunhofer-Institut für Angewandte Optik und Feinmechanik (Germany); J. Albero, S. Bargiel, CNRS FEMTO-ST (France); C. Schaeffel, Institut für Mikroelektronik- und Mechatronik- Systeme gemeinnützige GmbH (Germany); S. Beer, Ctr. Suisse d'Electronique et de Microtechnique SA (Switzerland); R. Moosburger, P. Lambelet, Heliotis Inc. (Switzerland); M. Pizzi, Techfab s.r.l. (Italy)
- 7718 0G **Automated multiscale measurement system for MEMS characterisation** [7718-15]
W. Lyda, A. Burla, T. Haist, J. Zimmermann, W. Osten, O. Sawodny, Univ. Stuttgart (Germany)
- 7718 0H **Simulation and in-plane movement characterization of 2D MEMS platform** [7718-16]
J. Kręzel, Institute of Micromechanics and Photonics (Poland); K. Laszczyk, S. Bargiel, C. Gorecki, FEMTO-ST Institute, UMR CNRS (France); M. Kujawińska, Institute of Micromechanics and Photonics (Poland); O. Parriaux, Lab. Hubert Curien, UMR CNRS (France); S. Tonchev, Institute of Solid State Physics (Bulgaria)

SESSION 5 TOPOGRAPHY AND SURFACE MEASUREMENTS

- 7718 0I **Multiresolution analysis of 2D confocal microscope images** [7718-17]
D. Bianchi, Austrian Ctr. of Competence for Tribology (Austria); A. Vernes, Austrian Ctr. of Competence for Tribology (Austria) and Vienna Univ. of Technology (Austria); G. Vorlaufer, Austrian Ctr. of Competence for Tribology (Austria); G. Betz, Vienna Univ. of Technology (Austria)
- 7718 0J **Comparability and uncertainty of shape measurements with white-light interferometers** [7718-18]
S. Boedecker, W. Bauer, Polytec GmbH (Germany); R. Krüger-Sehm, Physikalisch-Technische Bundesanstalt (Germany); P. H. Lehmann, Univ. Kassel (Germany); C. Rembe, Polytec GmbH (Germany)
- 7718 0L **Modelling the colour of a coated rough-steel surface** [7718-20]
V. Goossens, E. Stijns, Vrije Univ. Brussel (Belgium); S. Van Gils, ArcelorMittal Research Industry Gent (Belgium); R. Finsy, H. Terryn, Vrije Univ. Brussel (Belgium)
- 7718 0M **Measurements of characteristic parameters of extremely small cogged wheels with low module by means of low-coherence interferometry** [7718-21]
A. Pakula, S. Tomczewski, A. Skalski, D. Biało, L. Salbut, Warsaw Univ. of Technology (Poland)

SESSION 6 INSPECTION OF MICROOPTICS

- 7718 0N **Optical characterization of semiconductor microlenses using a Mach-Zehnder interferometer in the near-infrared region (Invited Paper) [7718-22]**
H. Ottevaere, N. Vermeulen, V. Gomez, H. Thienpont, Vrije Univ. Brussel (Belgium)
- 7718 0O **Sensitivity enhancement of bimaterial MOEMS thermal imaging sensor array using 2-λ wavelength readout [7718-23]**
O. Ferhanoğlu, H. Urey, Koç University (Turkey)
- 7718 0P **Characterization and inspection of micro-lens array by SCBS microscope [7718-24]**
W. Qu, O. C. Chee, Ngee Ann Polytechnic (Singapore); Y. Yu, Shanghai Univ. (China);
H. L. Ng-Lee, Ngee Ann Polytechnic (Singapore); A. Tian, Xi'an Technological Univ. (China);
A. Asundi, Nanyang Technological Univ. (Singapore)
- 7718 0Q **Multispectral characterization of diffractive micromirror arrays [7718-25]**
D. Berndt, J. Heber, S. Sinning, D. Kunze, J. Knobbe, Ju. Schmidt, M. Bring, D. Rudloff,
M. Friedrichs, J. Rößler, M. Eckert, W. Kluge, H. Neumann, M. Wagner, H. Lakner,
Fraunhofer-Institut für Photonische Mikrosysteme (Germany)
- 7718 0S **Unification of approaches to optimization and metrological characterization of continuous-relief diffractive optical elements [7718-27]**
V. P. Korolkov, S. V. Ostapenko, R. K. Nasirov, A. S. Gutman, A. R. Sametov, Institute of Automation and Electrometry (Russian Federation)

SESSION 7 ADVANCED MICROSCOPY TECHNIQUES

- 7718 0T **Multi-wavelength digital holographic microscopy for high-resolution inspection of surfaces and imaging of phase specimen (Invited Paper) [7718-47]**
S. Kosmeier, P. Langehanenberg, S. Przibilla, G. von Bally, B. Kemper, Univ. of Münster (Germany)
- 7718 0U **Advances in the development of the LNE metrological atomic force microscope [7718-28]**
B. Poyet, Lab. National de Metrologie et d'Essais (France) and Lab. d'Ingénierie des Systèmes de Versailles (France); S. Ducourtieux, Lab. National de Metrologie et d'Essais (France)
- 7718 0V **Millimeter scale topographical image of highly integrated optical structures using enlarged metrological atomic-force microscopy [7718-29]**
S. Topsu, L. Chassagne, A. Sinno, P. Ruaux, Y. Alayli, Lab. d'Ingénierie des Systèmes de Versailles (France) and Univ. de Versailles (France); G. Lerondel, S. Blaize, A. Bruyant, P. Royer, Institut Charles Delaunay, LNIO (France) and Univ. de Technologie Troyes (France)
- 7718 0X **One-shot measurement of surface profile using an astigmatic microscope system [7718-31]**
C.-S. Kang, Korea Research Institute of Standards and Science (Korea, Republic of);
J.-U. Lee, Cheongju Univ. (Korea, Republic of); J. W. Kim, J.-A. Kim, J. Jin, T. B. Eom, Korea Research Institute of Standards and Science (Korea, Republic of)

- 7718 0Y **Test objects for calibration of SEMs and AFMs operating at the nanoscale** [7718-32]
V. P. Gavrilenko, Ctr. for Surface and Vacuum Research (Russian Federation) and Moscow Institute of Physics and Technology (Russian Federation); Y. A. Novikov, Moscow Institute of Physics and Technology (Russian Federation) and A. M. Prokhorov General Physics Institute (Russian Federation); A. V. Rakov, Ctr. for Surface and Vacuum Research (Russian Federation); P. A. Todua, Ctr. for Surface and Vacuum Research (Russian Federation) and Moscow Institute of Physics and Technology (Russian Federation)

SESSION 8 INSPECTION OF MEMS II

- 7718 0Z **Digital reflection holography based systems development for MEMS testing** [7718-33]
V. R. Singh, S. Liansheng, A. Asundi, Nanyang Technological Univ. (Singapore)
- 7718 10 **Measuring ultra-sonic in-plane vibrations with the scanning confocal heterodyne interferometer** [7718-35]
C. Rembe, F. Ur-Rehman, F. Heimes, S. Boedecker, A. Dräbenstedt, Polytec GmbH (Germany)

SESSION 9 IMAGE RECONSTRUCTION AND SIGNAL PROCESSING

- 7718 13 **Motion detection using speckle photography and extended fractional Fourier transform** [7718-38]
B. Bhaduri, C. J. Tay, C. Quan, National Univ. of Singapore (Singapore)
- 7718 14 **Electromagnetic prediction of multiscale depolarization** [7718-39]
M. Zerrad, J. Sorrentini, G. Soriano, C. Amra, Institut Fresnel, UMR CNRS (France) and Aix-Marseille Univ., Ecole Centrale Marseille (France) and Faculté des Sciences et Techniques de Saint Jérôme (France)
- 7718 16 **Error analysis of 3D sheargraphy using finite-element modelling** [7718-41]
D. T. Goto, Technische Univ. Delft (Netherlands) and Univ. Federal de Santa Catarina (Brazil); R. M. Groves, Technische Univ. Delft (Netherlands)
- 7718 17 **Phase retrieval in ESPI from a dense phase fringe pattern** [7718-42]
H. Niu, C. Quan, C. J. Tay, National Univ. of Singapore (Singapore)

SESSION 10 SPECIALISED TECHNIQUES AND SENSORS

- 7718 18 **Narrow-selection bandwidth of femtosecond laser comb with application to changes in optical path distance** [7718-43]
R. Šmid, J. Ježek, Z. Buchta, M. Čížek, J. Lazar, O. Číp, Institute of Scientific Instruments of the ASCR, v.v.i. (Czech Republic)
- 7718 19 **Investigations of fast-rotating bodies using an interferometric laser Doppler distance sensor system** [7718-44]
P. Günther, F. Dreier, T. Pfister, J. Czarske, T. Haupt, M. Gude, W. Hufenbach, Technische Univ. Dresden (Germany)

- 7718 1B **Accuracy of ellipsometric measurements of Si-SiO₂ structures** [7718-46]
V. P. Gavrilenko, Ctr. for Surface and Vacuum Research (Russian Federation) and Moscow Institute of Physics and Technology (Russian Federation); Y. A. Novikov, Moscow Institute of Physics and Technology (Russian Federation) and A. M. Prokhorov General Physics Institute (Russian Federation); A. V. Rakov, Moscow Institute of Physics and Technology (Russian Federation); P. A. Todua, Ctr. for Surface and Vacuum Research (Russian Federation) and Moscow Institute of Physics and Technology (Russian Federation)
- 7718 1C **An optical microform calibration system for ball-shaped hardness indenters** [7718-48]
Z. Li, S. Gao, K. Herrmann, Physikalisch-Technische Bundesanstalt (Germany)

SESSION 11 PROCESS MONITORING SYSTEMS

- 7718 1D **Optical metrology for process control: modeling and simulation of sensors for a comparison of different measurement principles** [7718-49]
D. Fleischle, W. Lyda, F. Mauch, W. Osten, Univ. Stuttgart (Germany)
- 7718 1E **Scatterometric analysis of chatter marks occurring in industrial grinding processes** [7718-50]
J. Böhm, Austrian Ctr. of Competence for Tribology (Austria); A. Vernes, Austrian Ctr. of Competence for Tribology (Austria) and Technische Univ. Wien (Austria); M. Jech, Austrian Ctr. of Competence for Tribology (Austria); M. Vellekoop, Technische Univ. Wien (Austria)
- 7718 1F **An optically non-destructive, non-contact, and vibration-insensitive edge quality assessment system for semiconductor and harddisk drive industries** [7718-51]
S. Sumridetchkajorn, K. Chaitavon, National Electronics and Computer Technology Ctr. (Thailand)
- 7718 1G **Optical coherent sensor for monitoring and measurement of engineering structures** [7718-52]
D. Łukaszewski, L. Satbut, Warsaw Univ. of Technology (Poland); J. A. Dziuban, Wroclaw Univ. of Technology (Poland)
- 7718 1H **Highly sensitive wavefront sensor for visual inspection of bare and patterned silicon wafers** [7718-53]
I. Lazareva, A. Nutsch, M. Schellenberger, L. Pfitzner, L. Frey, Fraunhofer-Institut für Integrierte System und Bauelementetechnologie (Germany)

POSTER SESSION

- 7718 1I **Semi-derivative real filter for the measurement of the wavefront distortion** [7718-54]
R. Kasztelanic, M. Barański, Univ. of Warsaw (Poland)
- 7718 1J **In situ control of roughness of processed surfaces by reflectometric method** [7718-55]
Y. D. Filatov, O. Yu. Filatov, Bakul Institute for Superhard Materials (Ukraine); U. Heisel, M. Storchak, Univ. Stuttgart (Germany); G. Monteil, National Engineering Institute in Mechanics and Microtechnologies (France)
- 7718 1L **A micro-SPM head array for large-scale topography measurement** [7718-57]
S. Gao, Z. Li, K. Herrmann, Physikalisch-Technische Bundesanstalt (Germany)

- 7718 1M **Simple methods for alignment of line distance sensor arrays** [7718-58]
H. Bremer, F. Schmähling, C. Elster, Physikalisch-Technische Bundesanstalt (Germany);
S. Krey, A. Ruprecht, TRIOPTICS GmbH (Germany); M. Schulz, M. Stavridis, A. Wiegmann,
Physikalisch-Technische Bundesanstalt (Germany)
- 7718 1P **Optical testing of bifocal diffractive-refractive intraocular lenses using Shack-Hartmann
wavefront sensor** [7718-61]
A. S. Gutman, JSC IntraOL (Russian Federation); I. V. Shchesyuk, V. P. Korolkov, Institute of
Automation and Electrometry (Russian Federation)

Author Index

Conference Committee

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Keynote Session
Christophe Gorecki, Université de Franche-Comté (France)

- 1 Digital Holography
Wolfgang Osten, Universität Stuttgart (Germany)
- 2 New Aspects in Microtopography Measurements I
Kay Gastinger, SINTEF (Norway)
- 3 New Aspects in Microtopography Measurements II
Kay Gastinger, SINTEF (Norway)

- 4 Inspection of MEMS I
Christophe Gorecki, Université de Franche-Comté (France)
- 5 Topography and Surface Measurements
Malgorzata Kujawinska, Politechnika Warszawska (Poland)
- 6 Inspection of Microoptics
Anand Krishna Asundi, Nanyang Technological University (Singapore)
- 7 Advanced Microscopy Techniques
Heidi Ottevaere, Vrije Universiteit Brussel (Belgium)
- 8 Inspection of MEMS II
Anand Krishna Asundi, Nanyang Technological University (Singapore)
- 9 Image Reconstruction and Signal Processing
Pietro Ferraro, Istituto Nazionale di Ottica Applicata (Italy)
- 10 Specialised Techniques and Sensors
Heidi Ottevaere, Vrije Universiteit Brussel (Belgium)
- 11 Process Monitoring Systems
Leszek A. Salbut, Politechnika Warszawska (Poland)